

Low temperature electrical characteristics of irradiated strip sensors

J.Bohm, Z.Dolezal, P.Masek, M.Solar

Academy of Sciences of the CR

Charles University, Prague

Czech Technical University, Prague

CONTENT

Irradiation of ATLAS07 miniature sensors on reactor in Rez near Prague

Experimental set-up for temperature -30deg C

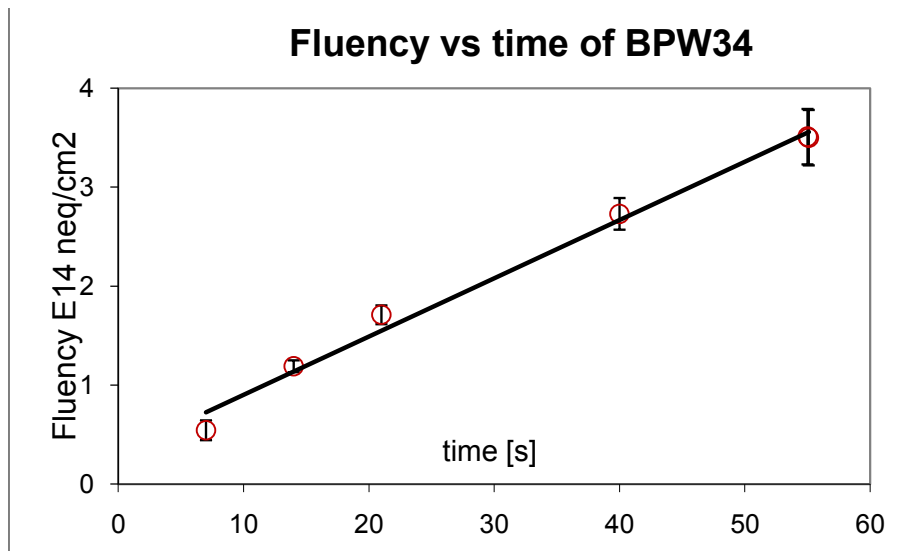
Bulk IV and CV characteristics

Coupling and an inter-strip capacitance

Punch through voltage measured by DC method

Irradiation of sensors on reactor LVR15

An exposition time was calibrated by diodes BPW34 from CERN
 Fluency Φ [neq/cm²/mV]=9.1E09*(Virr--Vo),
 where Virr and Vo are voltages generating current of 1mA at 20°C in open direction.



Pneumatic transport of sensors in the channel H1.

Mini-sensor is closed in PVC envelopes which is placed inside plastic tube $\varnothing=3\text{cm}$ and length of 8cm.

There is no cooling in the channel H1 and therefore after 3 min the tube with sensor must be removed from reactor due to high temperature ($\sim 55^\circ\text{C}$) and cooled before next step of irradiation

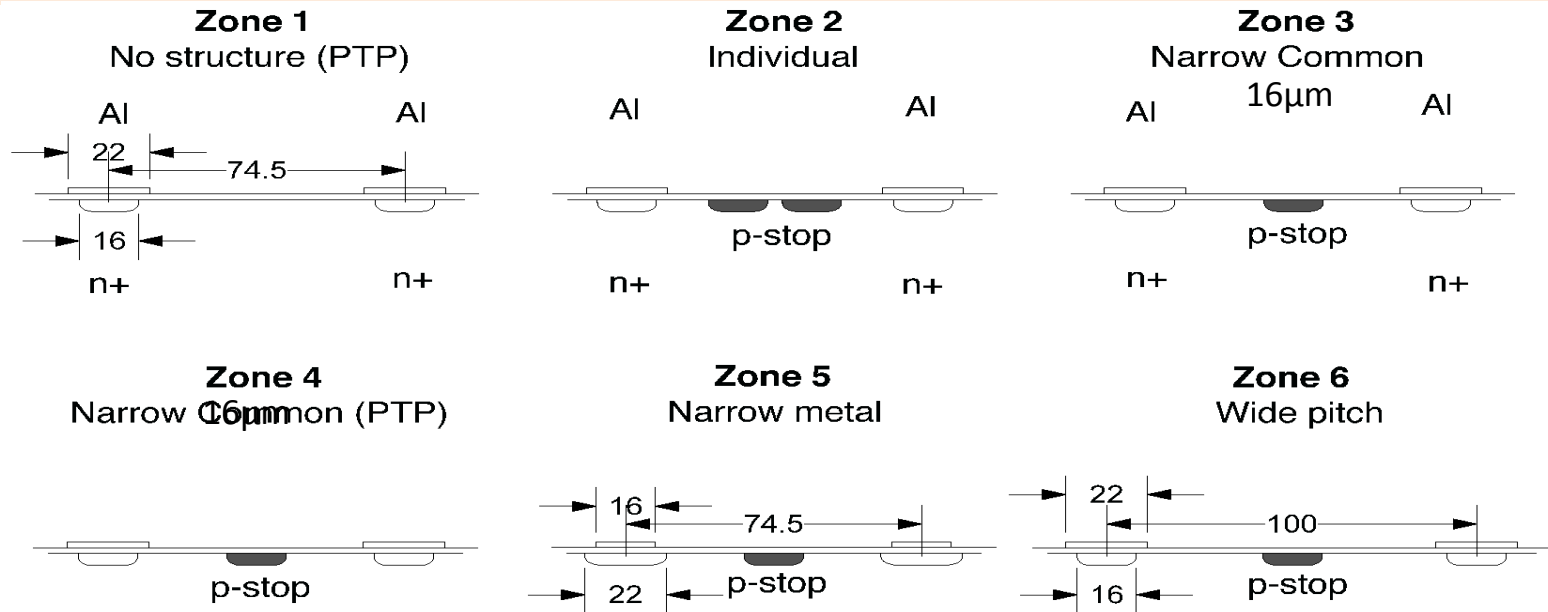
Fluency rate on LVR15 at 9.9MW

4E14	2E15	1E16
W12BZ4AP4	W13BZ4AP4	W13BZ1P7
W12BZ4BP10	W13BZ4BP10	W13BZ2P2
W12BZ4CP16	W13BZ4CP16	W13BZ5P11
W12BZ4DP22	W13BZ4DP22	W13BZ6P22

Fluence neq/cm²	Exposition seconds	3min irrad
4E14	54.6	1x
2E15	272.9	2x
1E16	1364	8x

Annealing: ~60 days at 23C

Basic sensor characteristics



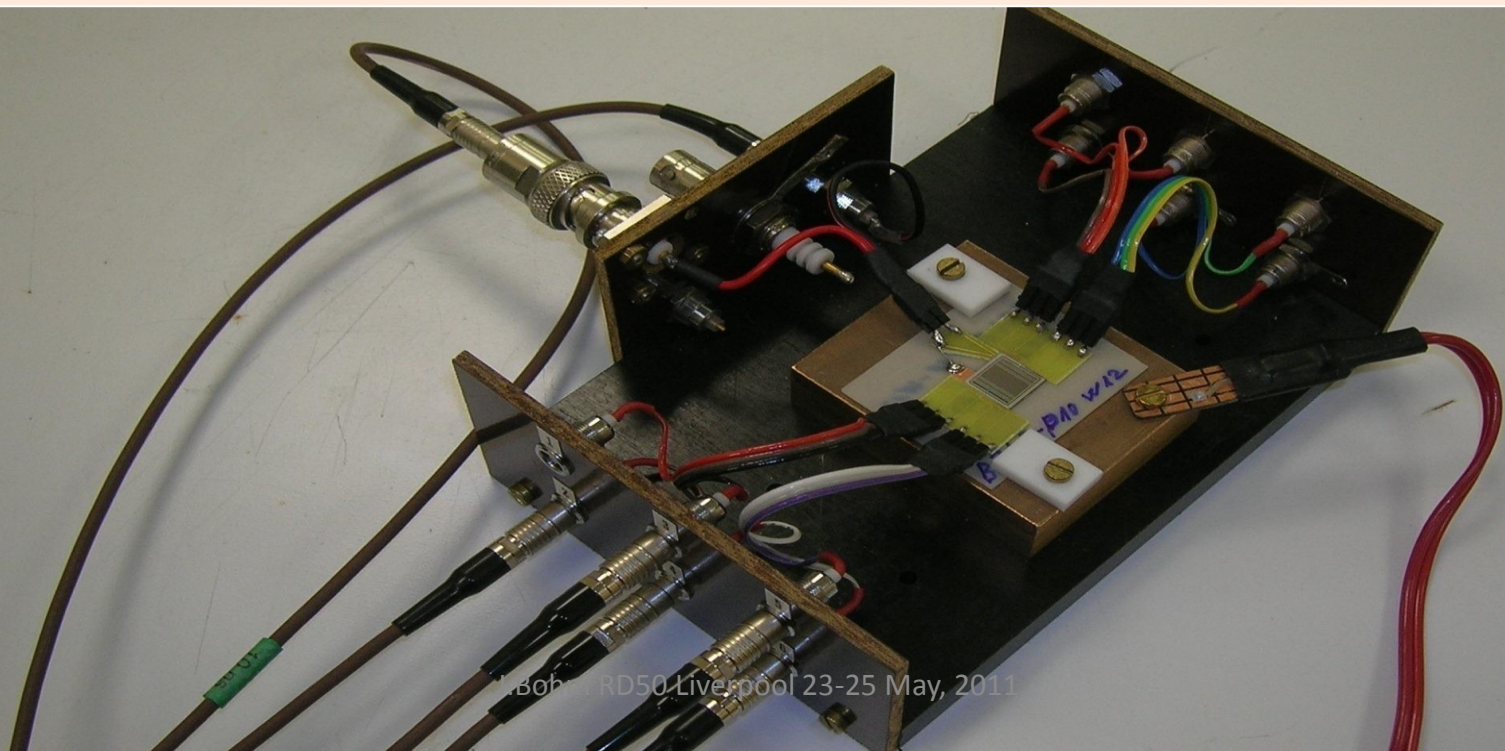
The micro-strip silicon **miniature sensors of 1cmx1cm** (strip length 0.8cm) are ATLAS07 Series I fabricated by Hamamatsu Photonics (HPK) using 6" (150 mm) process technology . The baseline is **p-type** float zone silicon of resistance $\sim 6.7k\Omega$ with crystal orientation $\langle 100 \rangle$ and having **thickness of 320 µm**. Sensors are single-sided with capacitively coupled readout **n-type strips** which are biased through polysilicon resistors. The readout strips with **pitch 74.5 µm** are electrically isolated by a common and floating p-implant (**'p-stop' isolation**) with doping concentration of **$1 \times 10^{12} \text{ions/cm}^2$** (wafers W12 and W13)

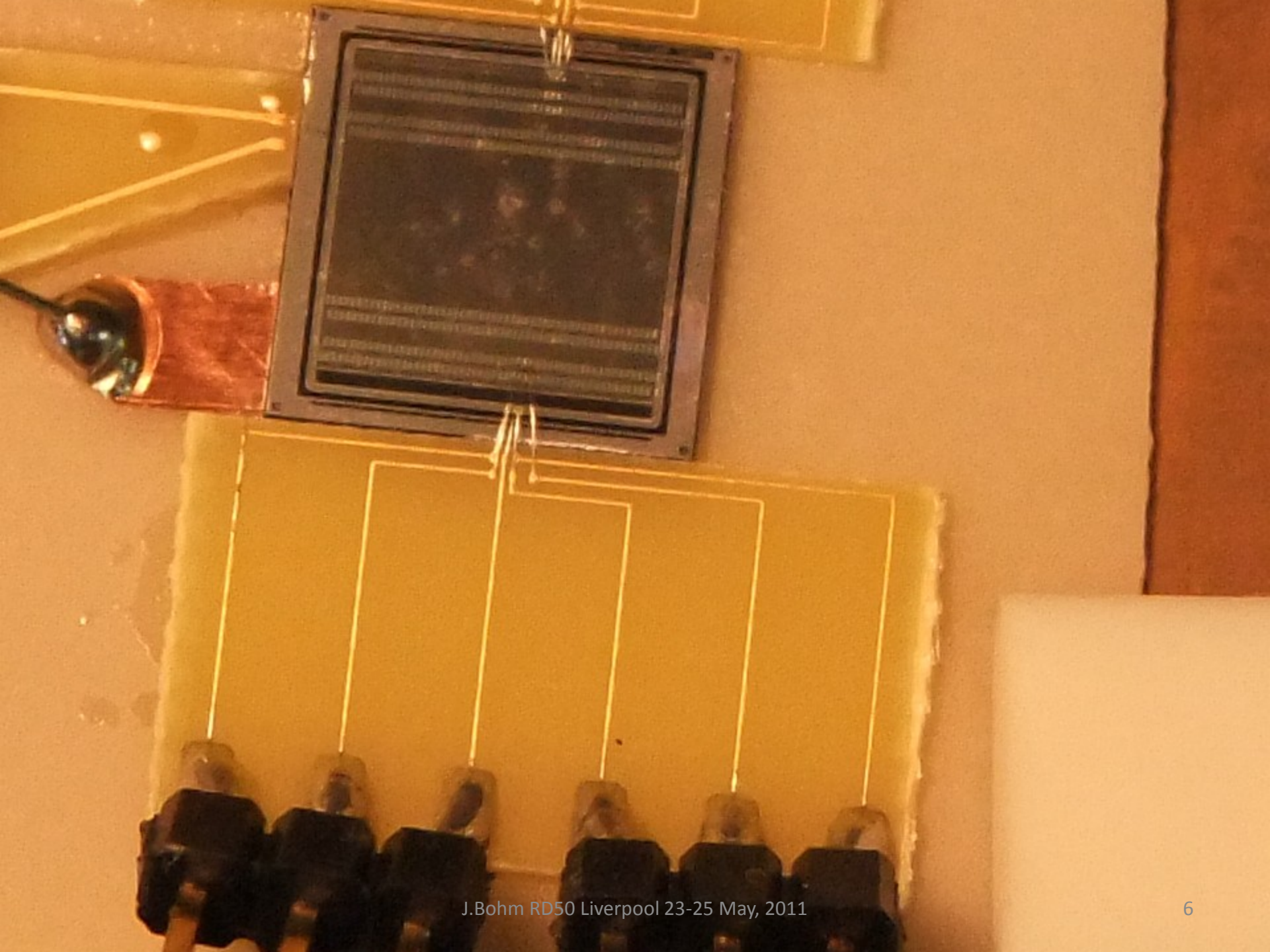
EXPERIMENTAL SET-UP FOR TEMPERATURE -30 C

Measurement of the sensor basic characteristics at working temperature -30C which is supposed for upgraded ATLAS ID at sLHC.

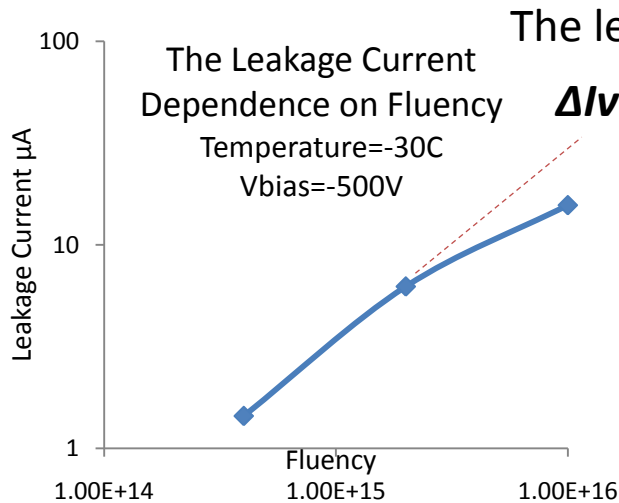
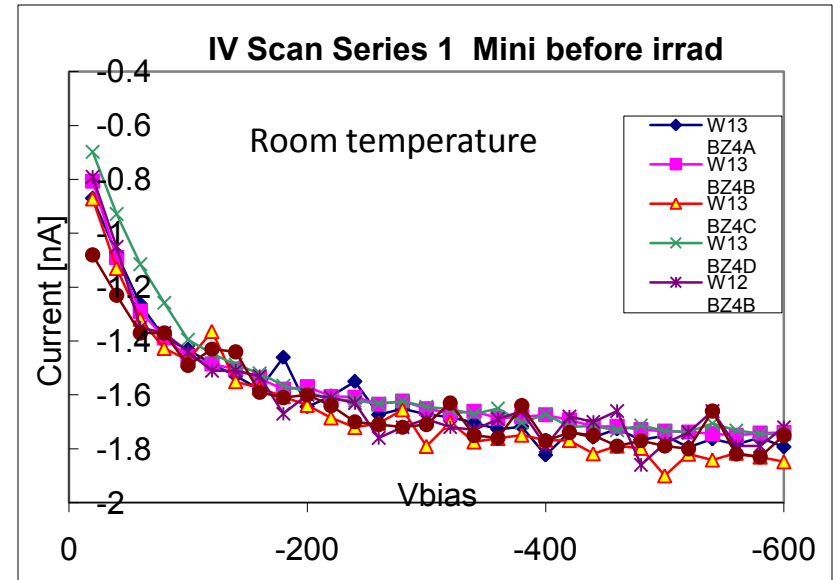
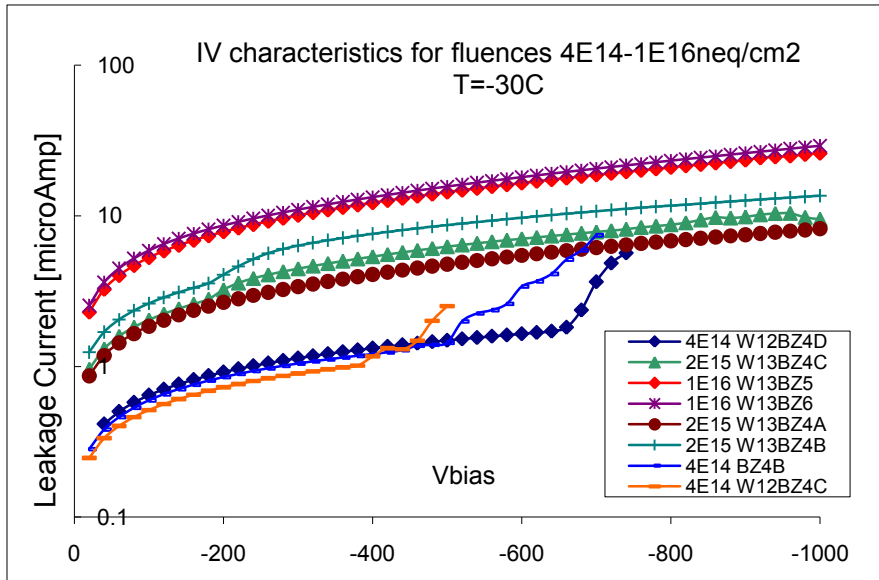
Six AC and DC pads of the randomly selected neighboring strips are bonded to PCB and contacted to connectors . Ceramic plate 0.4mm with high heat conductivity is placed on Cu-cube. The Cu-tape serves as the backplane electrode glued to sensor.

Results are still preliminary





BULK IV AND CV CHARACTERISTICS

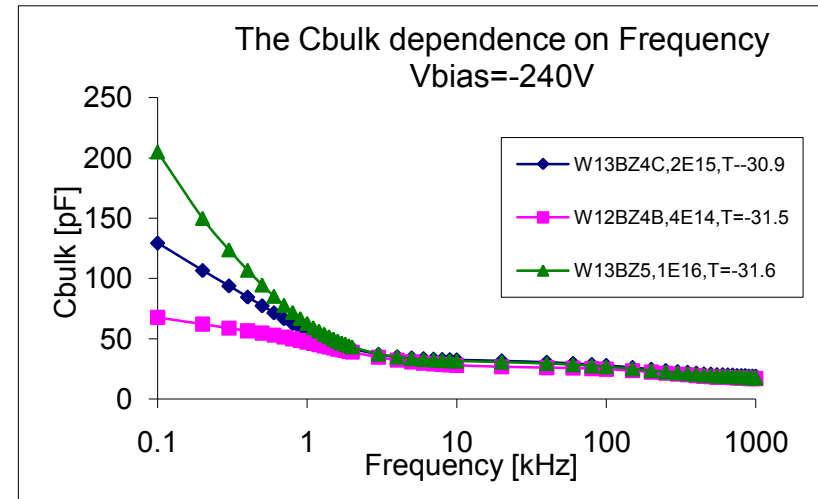
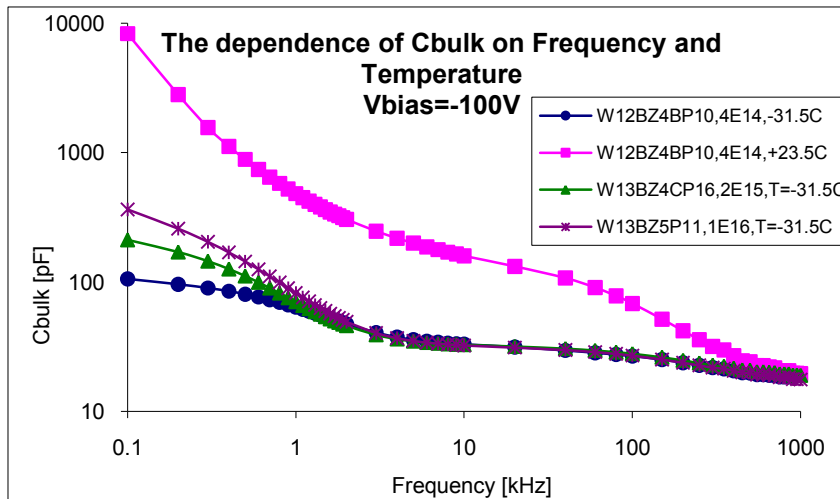


The leakage current is increasing with fluency as it was expected

$\Delta I_{vol}/V = \alpha \Phi$ is valid for fluences lower than $\sim 10^{13}$ neq/cm2

The lower leakage current for fluency 10^{16} neq/cm2 than one which could be expected from the linear dependence, needs confirmation.

Bulk CV Characteristics



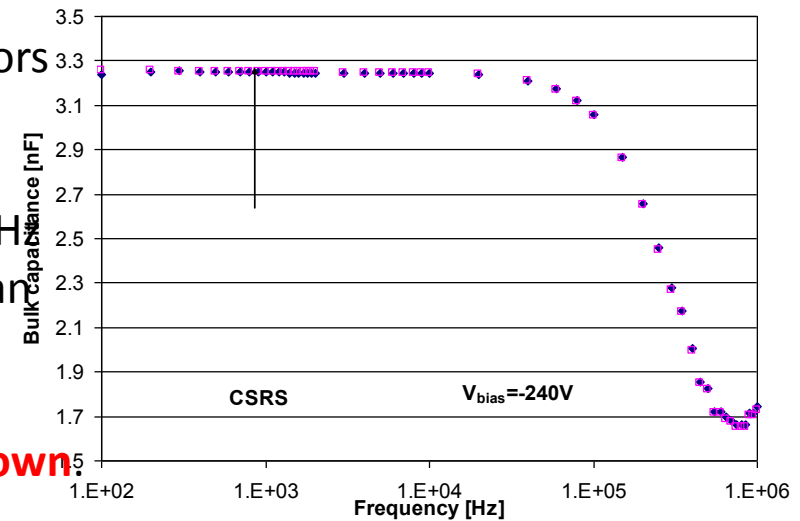
There is a big difference in the C_{bulk} frequency dependence of irradiated and non-irradiated sensors mostly in the **non-depleted region**.

-Above ~2kHz C_{bulk} does not depend on fluency

-C_{bulk} strongly depends on temperature: For 100H C_{bulk} at room temperature is 100 times higher than C_{bulk} after irradiation up to 4E14 but both capacitances are the same for 1MHz.

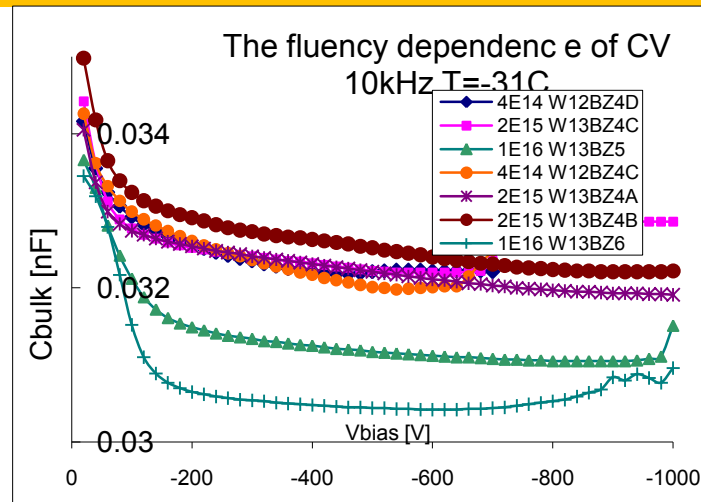
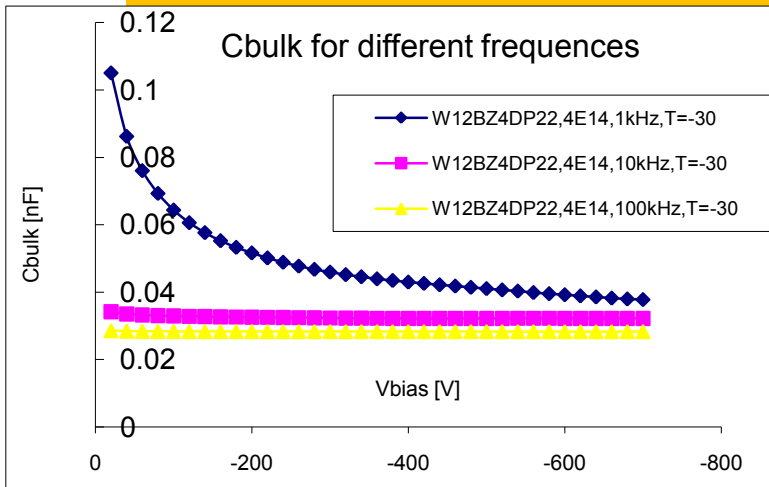
Photon /neutron ratio on reactor in Rez is not known

Radiation damage in the surface region?

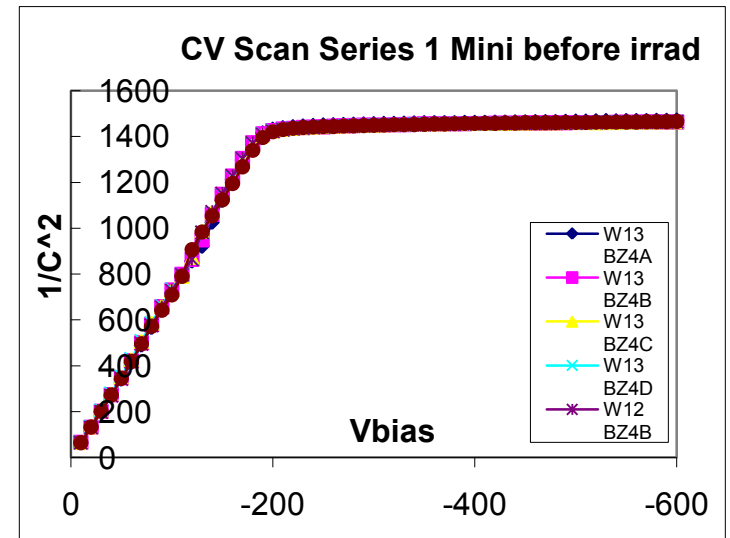
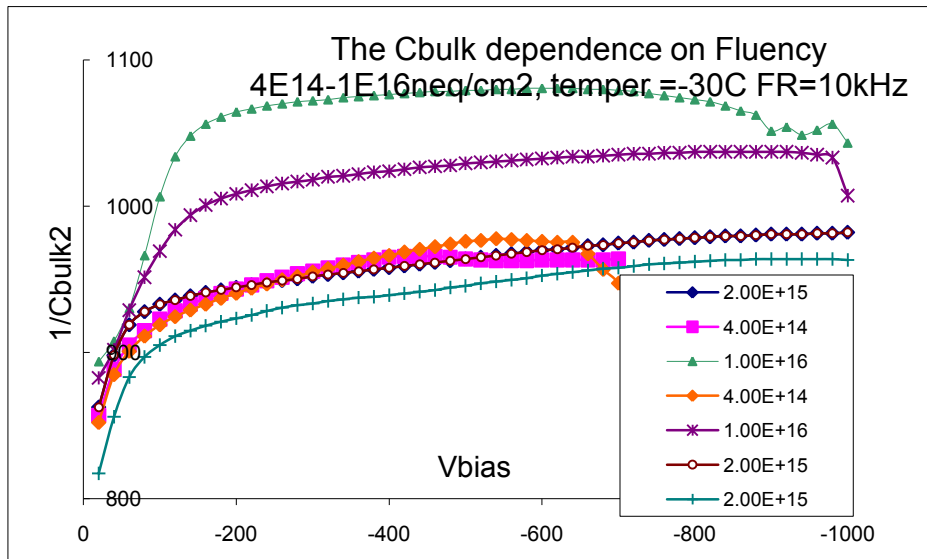


Room temperature, non-irrad, V_{bias} = 240V

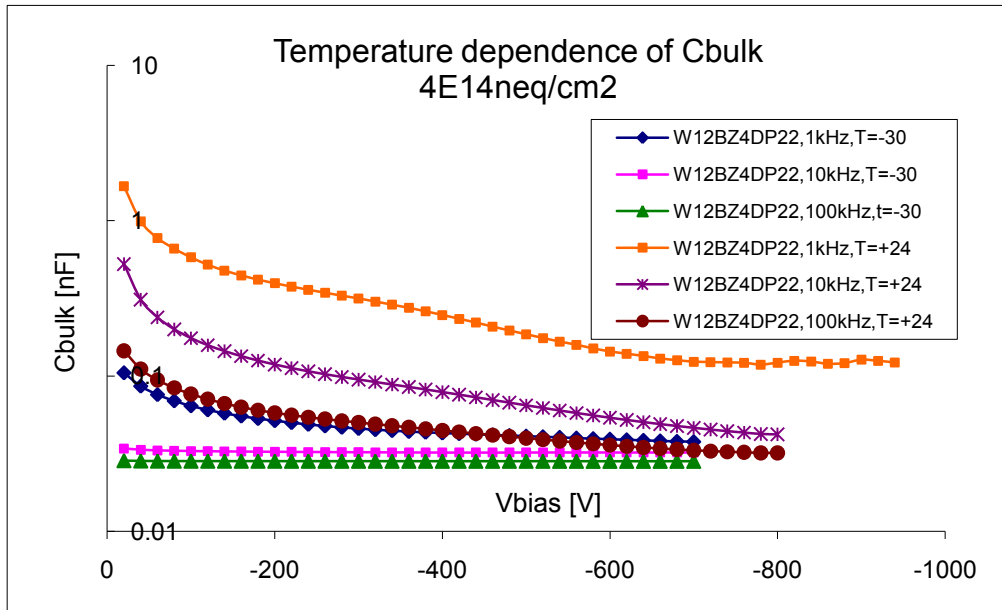
BULK CV CHARACTERISTICS



The Vbias dependence of Cbulk for 10kHz is different for various fluences
Vfd for various fluences seems to be even lower than one for non-irradiated sensors after long annealing. It will be checked by CC measurement with laser.

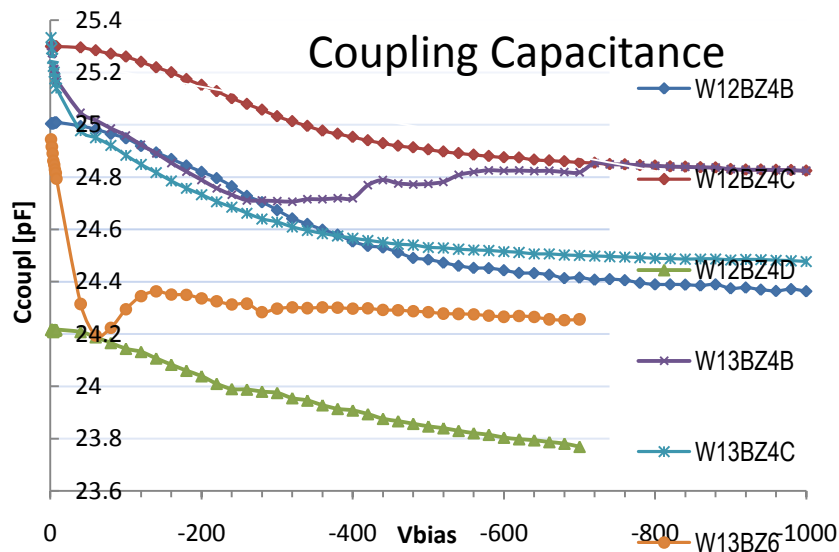
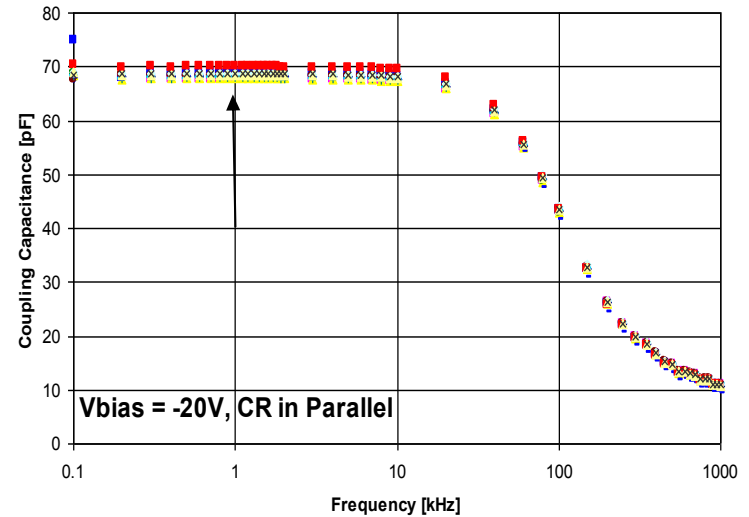
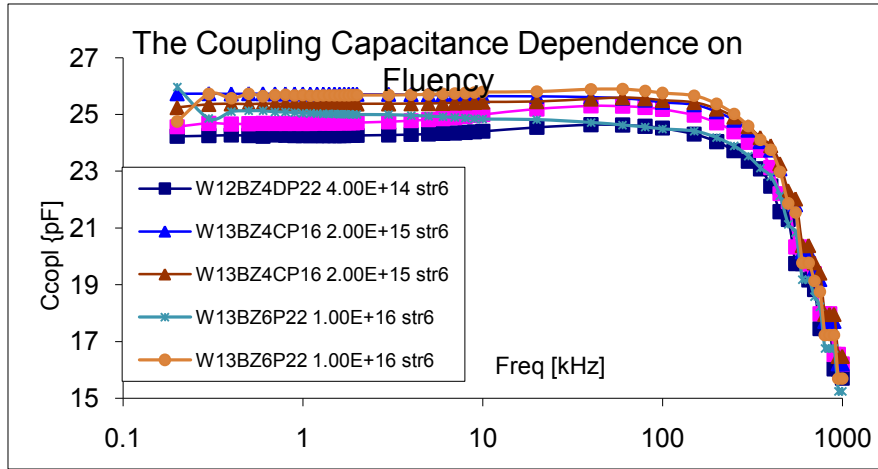


Bulk CV Characteristics



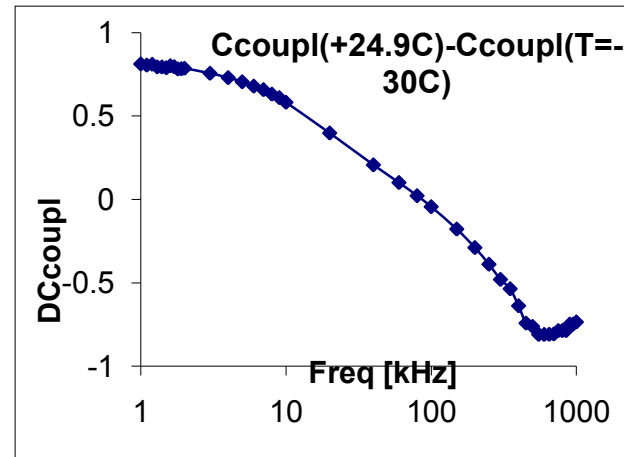
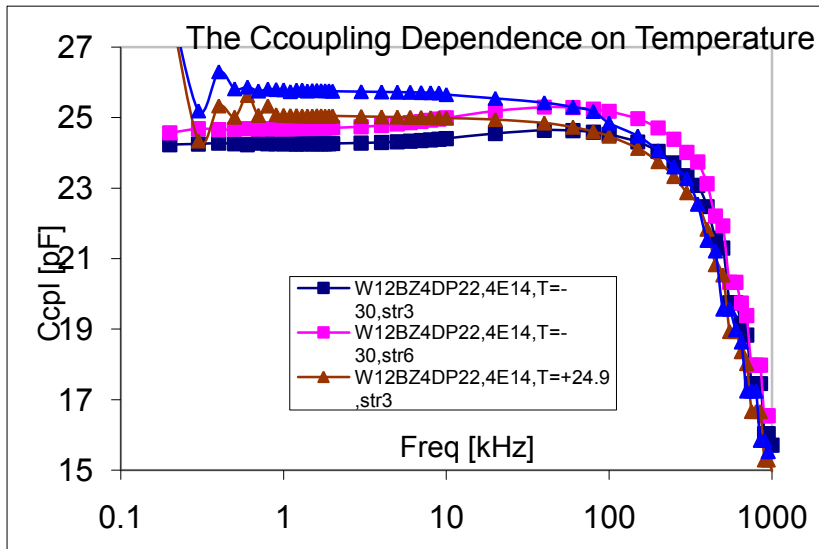
Behavior of C_{bulk} characteristics needs more delicate investigation

Coupling Capacitance



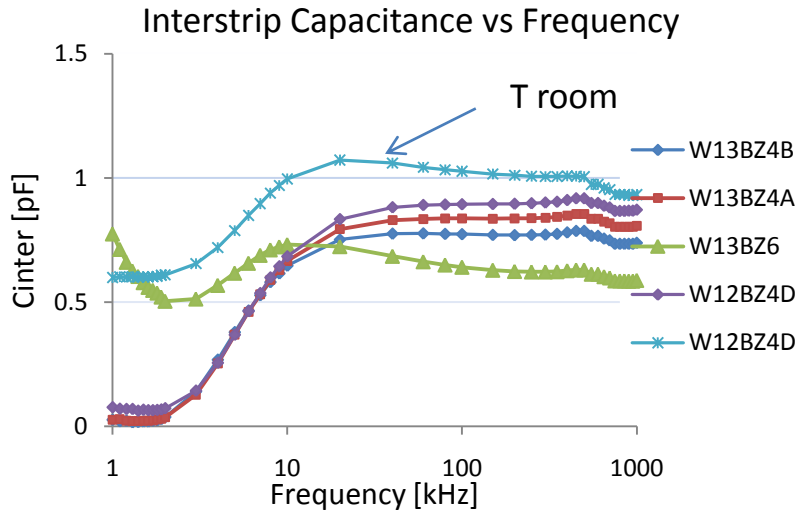
Frequency characteristic of C coupling is flat up to 100kHz for irradiated sensors and it does not depend on fluency.
 $\langle C_{\text{coupl}} \rangle = 30\text{pF/cm}$

Coupling Capacitance

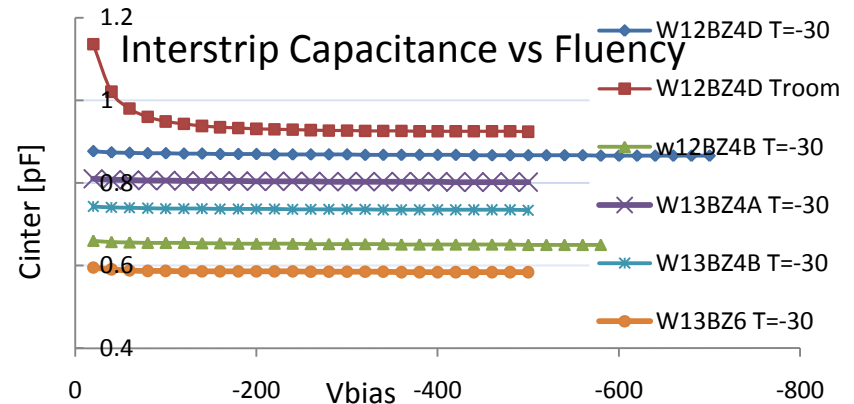
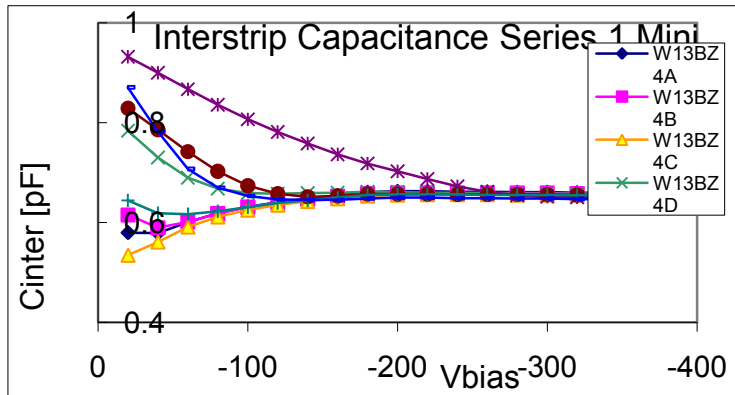
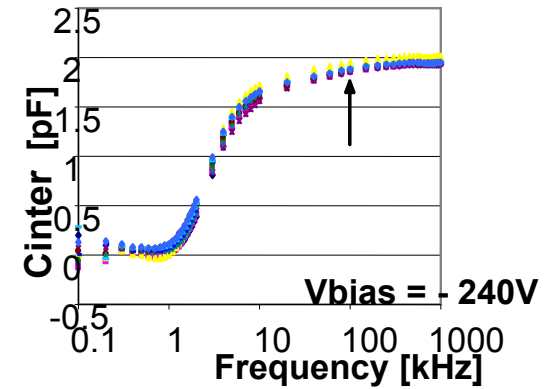


Temperature dependence of C_{cpl} is very weak

Interstrip Capacitance



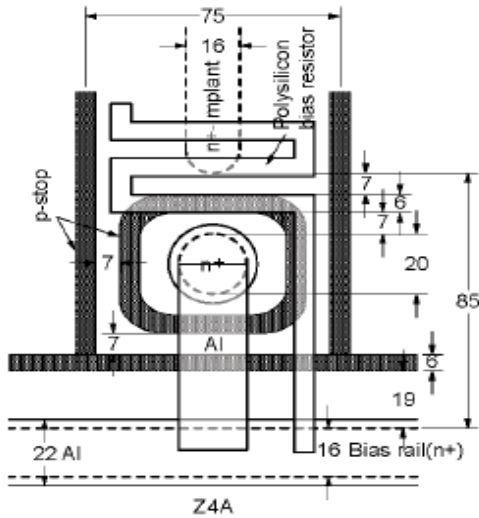
Non-irradiated full size sensors



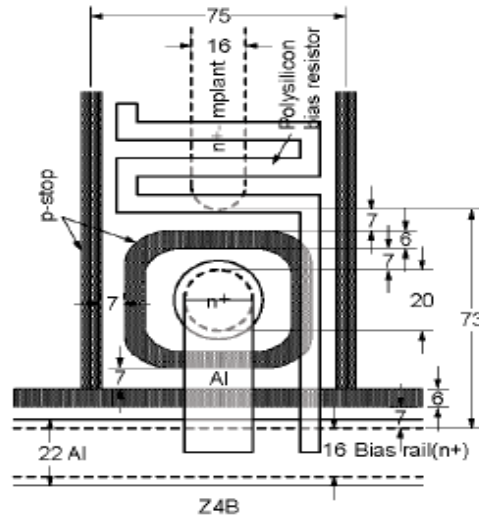
Weak dependence of the Interstrip Capacitance on fluency: $\langle C_{inter} \rangle = 0.9 \text{ pF/cm}$

Punch Through Protection Structures

Z4A



Z4B

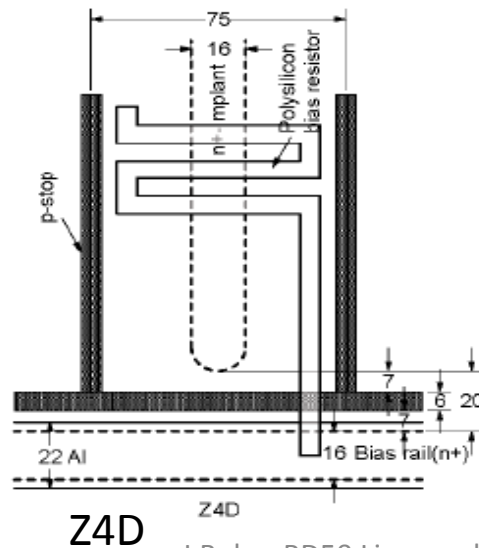
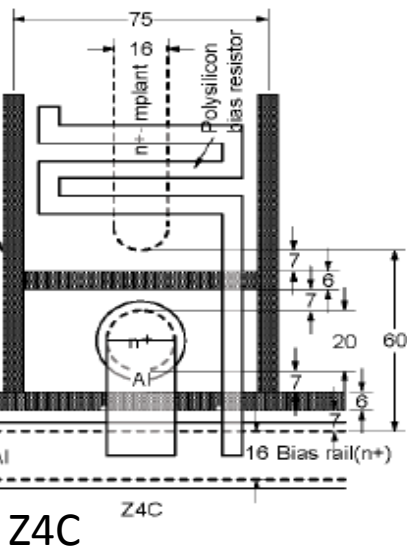


When a large amount of charge is deposit in the sensor by a beam splash, a large current flows through the bias resistor and drops the potential of the n-strips implant toward the backplane bias voltage, thus generating a spike of voltage across the AC coupling insulator.

Z4A

Z4B

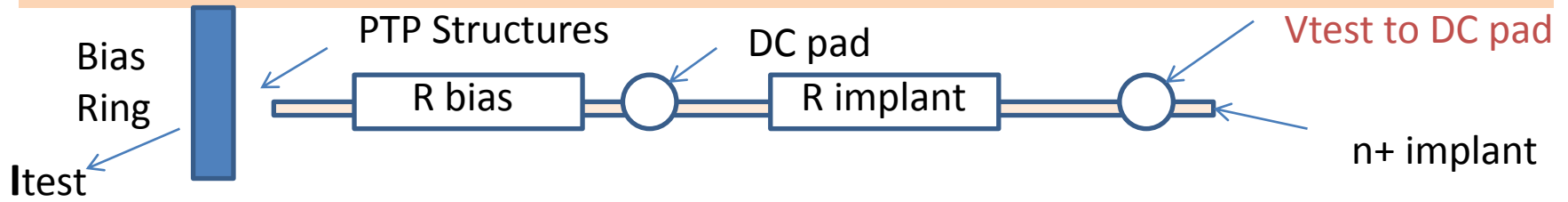
When the distance between the bias rail and the n-strip implants is appropriate, this voltage between the bias rail and the n-strip implants can be limited. This distance is 20 μm.



Z4C

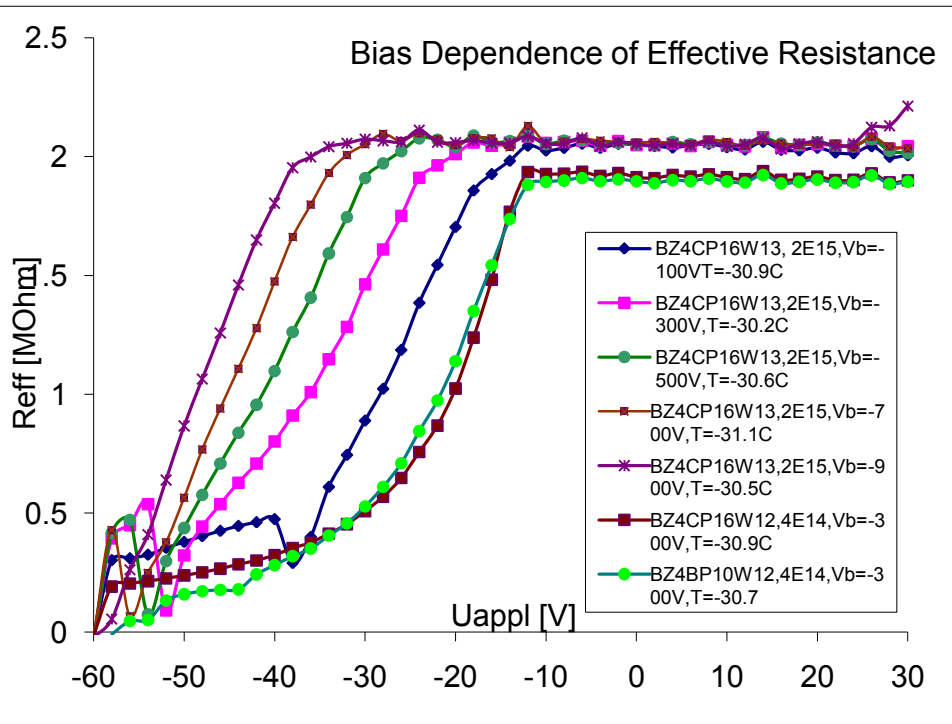
Z4D

Punch Through Protection - DC-method



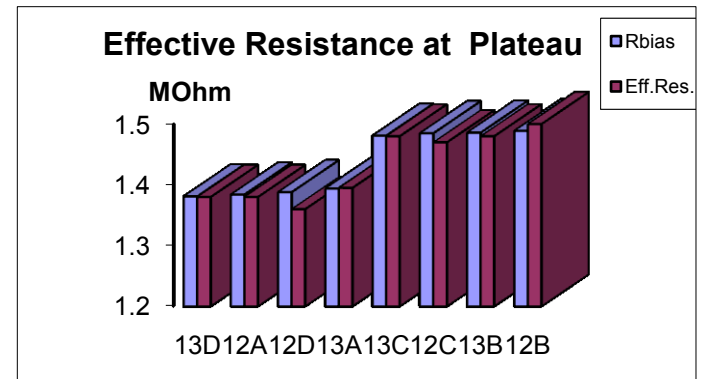
$R_{eff} = V_{test} / I_{test}$, where V_{test} is an applied voltage (U_{appl}) to DC pad and I_{test} is an current between DC pad and the bias ring. R_{pt} is supposed to be parallel to R_{bias}

Punch-Through Voltage is the Test Voltage for $R_{bias} = R_{pt}$, i.e. for $R_{eff} = R_{bias} / 2$

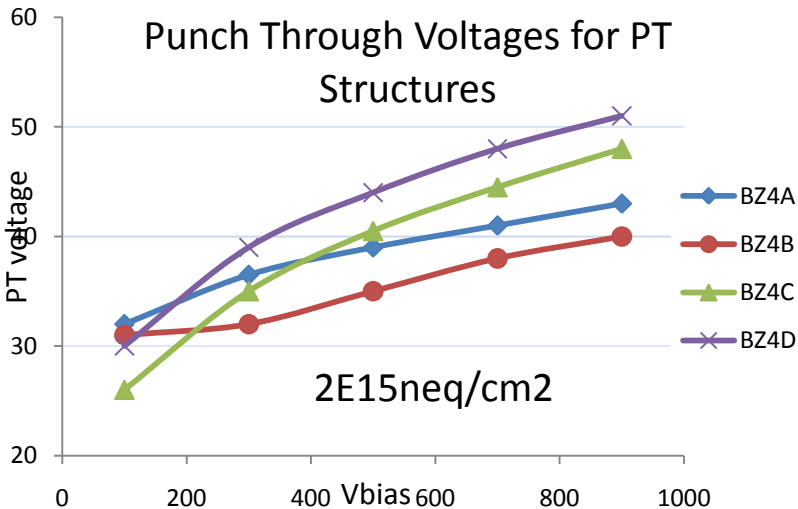
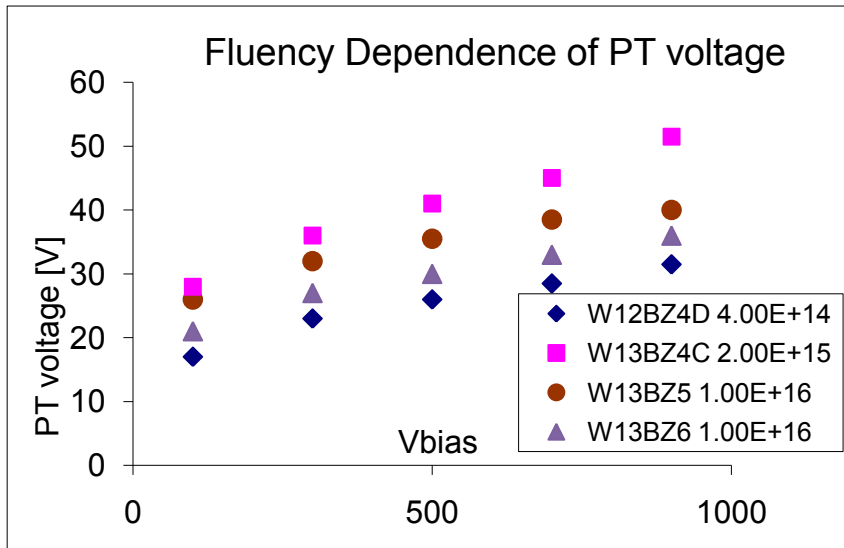


$$R_{eff} = 1 / (1/R_{bias} + 1/R_{PT})$$

Sensors before irradiation

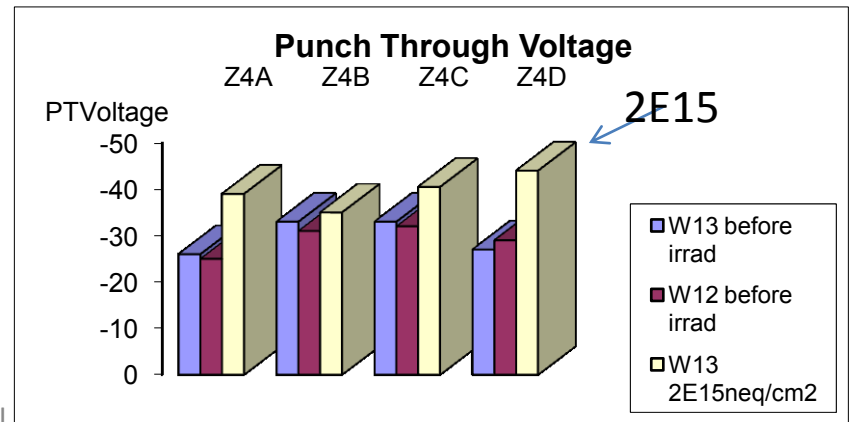


Punch Through Protection - DC-method

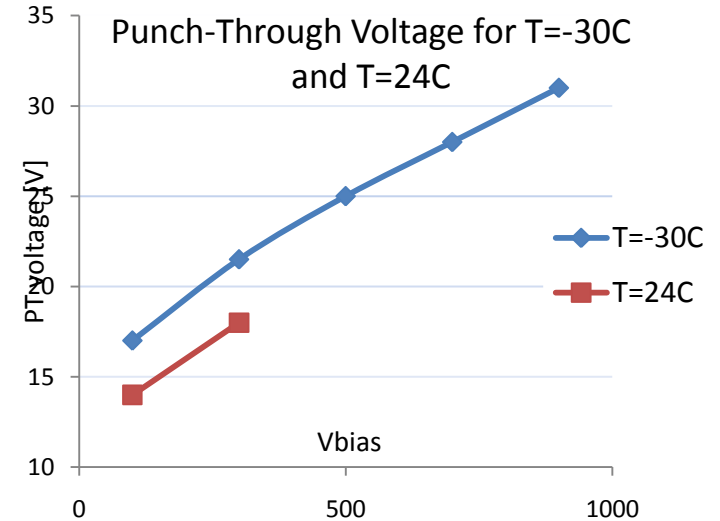
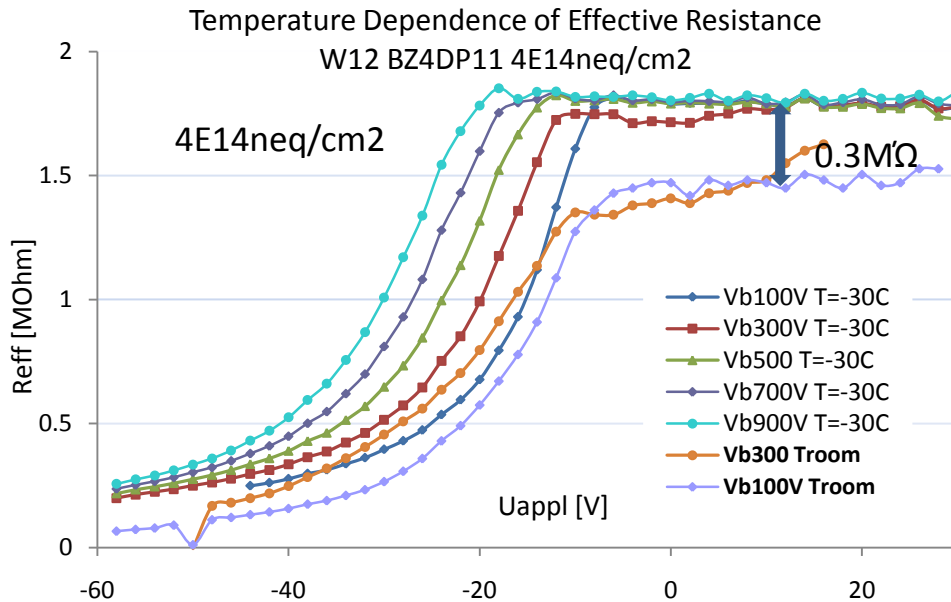


- PT voltage is increasing with bias voltage
- PT voltage is increasing with fluency
- PT voltage is higher for irradiated sensors than one for non-irradiated sensors.
- PT voltage for sensors Z4D and Z4C (the simplest PTP structure) is higher by ~10V than one for Z4A and Z4B.

There is no saturation of PT voltages even for $PTV \geq V_{fd}$. It agrees with the Santa Cruz result (C.Betancourt, Oxford, March 2011): ‘Finite implant resistance ($R_{imp}=19.4k\Omega$) isolates PTP structure from the far implant end.’



Temperature Dependence of Punch-Through Voltage?



PT voltage is slightly higher for low temperature (-30C) than for room temperature (24C). The difference would be explained by lower bias resistance for room temperature than for -30C.

It is worth to measure temperature dependence of bias resistor.

Conclusion

- * ATLAS07 Series I mini-sensors of HPK have been irradiated on reactor LVR15 in Rez up to three fluences: $4E14$, $2E15$ and $1E16 \text{neq/cm}^2$
- * Sensors were measured at temperature -30C which is planned for ID and sLHC
- * **A rise of the leakage current with fluency is not linear. Values at $1E16 \text{neq/cm}^2$ should be confirmed.**
- * **Above $\sim 2\text{kHz}$ C_{bulk} does not depend on fluency**
- * **C_{bulk} strongly depends on temperature**
- * **V_{fd} after 2 months annealing seems to be lower than one for non-irradiated sensors? Confirmation by CC measurement is needed**
- * **Frequency characteristic of C coupling does not depend on fluency and temperature: $\langle C_{\text{coupl}} \rangle = 30 \text{pF/cm}$**
- * **Weak dependence of the Interstrip Capacitance on fluency: $\langle C_{\text{inter}} \rangle = 0.9 \text{pF/cm}$**
- * **PT voltage is increasing with fluency.**
- * **There is no saturation of PT voltage even for $V_{\text{pt}} \geq V_{\text{fd}}$**
- * **An evidence that R_{bias} rises with decreasing temperature – it should be confirmed**

Measurement will continue also with a laser. More mini sensors are needed